

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

BAKKER et al.

Application No.: TO BE ASSIGNED

Group Art Unit: UNKNOWN

Filed: November 21, 2003

Examiner: UNKNOWN

Title: LITHOGRAPHIC PROJECTION APPARATUS WITH MULTIPLE
SUPPRESSION MESHES

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November 21, 2003

INFORMATION DISCLOSURE STATEMENT

MAIL STOP PATENT APPLICATION

Commissioner for Patents

P.O. BOX 1450

Alexandria, VA 22313-1450

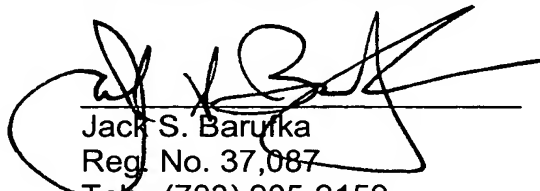
Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully submitted,

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| Atty. Dkt. No. | M# | Client Ref. |
| | 306794 | P-0388.010-US |

**INFORMATION DISCLOSURE STATEMENT
 BY APPLICANT**

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|--------------------------------|-----------------|
| Applicant: BAKKER et al. | |
| Appln. No.: TO BE ASSIGNED | |
| Filing Date: November 21, 2003 | |
| Examiner: | Group Art Unit: |

Date: November 21, 2003 Page 1 of 1

U.S. PATENT DOCUMENTS

| Examiner's Initials* | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
|-------------------------|--------------------|-----------------|---|-------|--------------|------------------------------------|
| | AR | | | | | |
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| | LR | | | | | |
| | MR | | | | | |
| | NR | | | | | |
| | OR | | | | | |

FOREIGN PATENT DOCUMENTS

| | Document Number | Date MM/YYYY | Country | Inventor Name | English Abstract | | Translation Readily Available | |
|--|--------------------|-----------------|---------|---------------|---------------------|----|-------------------------------------|----|
| | | | | | Enclosed | No | Enclose | No |
| | PR EP 1 182 510 A1 | 02/2002 | Europe | MOORS et al. | X | | | |
| | QR | | | | | | | |
| | RR | | | | | | | |
| | SR | | | | | | | |
| | TR | | | | | | | |
| | UR | | | | | | | |
| | VR | | | | | | | |

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

| | | | | |
|-----|---|--|--|--|
| WR | Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," <i>J. Vac. Sci. Technol. B</i> 12(6):3833-3840, XP-002096163 (1994) | | | |
| XR | | | | |
| YR | | | | |
| ZR | | | | |
| AAR | | | | |
| BBR | | | | |
| CCR | | | | |

Examiner Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.